TurboDisc GaN MOCVD System Comparison



LED Manufacturer Concern:

"LED manufacturing is very competitive due to industry consolidation and the decreasing price of LED bulbs. I am under pressure to lower manufacturing costs to protect my gross margins while adding capacity to my fab. We are running at about 90% capacity right now and need to add capacity to meet accelerating demand for general lighting adoption. Therefore, we need high productivity, high yield and reliable MOCVD systems."

Solutions:

Platform	Introduced	Reactor Size (mm)	4" Wafers	6" Wafers	Yield	Software Features	Productivity	Multi- Reactor Capable
EPIK700	2014	700	62 2 Reactors	24 2 Reactors	Best	Best	Best	√
MaxBright	2011	465	56 4 Reactors	24 4 Reactors	Better	Better	Better	√
K465i	2010	465	12	6	Better	Better	Good	

TurboDisc® MOCVD Product Release Timeline



K465i MOCVD System

- > Uniform gas injector FlowFlange® for improved flow distribution
- > Enhanced uniformity and yield
- > Improved ease-of-use
- > Nexus® control software



MaxBright® Multi-Reactor MOCVD System

- > Cluster tool in 2 or 4 chamber configuration
- > Central robot to transfer wafer carriers
- Modular frame and shared gas panel design
- > Nexus control software



EPIK700" MOCVD System

- > Up to 20% cost per wafer reduction compared to previous generations
- > Best-in-class uniformity drives greater yield in a tighter bin
- Highest productivity reactor generates
 2.5x throughput advantage compared to previous reactors
- Seamless process transfer from existing TurboDisc MOCVD systems



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